

Symposium S: Plasma processing of materials: from fundamentals to applications

Scope of the Symposium

The aim of this symposium is to bring together physicists, chemists, materials scientists, engineers and members of other scientific communities, offering a forum for discussions on advances of plasma processing of materials, from both experimental and theorical approaches, to facilitate the contact between science, technology and industry. Areas of particular interest will include, but will not be limited to: Fundamentals of deposition processes and techniques Experiments and simulations on plasma surface-interactions Plasma characterization Plasma Enhanced Chemical Vapor Deposition of protective coatings Atomic layer processes and 2D materials Plasma treatment of biomaterials Surface engineering via plasma processing Atmospheric pressure plasmas Applications of plasmas in agriculture, medicine and environmental sciences.

Abstracts will be solicited in (but not limited to) the following areas

- Plasma-surface interactions
- PECVD
- Plasma polymerization
- Plasma immersion ion implantation and deposition
- Plasma etching and sputtering
- Plasma electrolytic oxidation
- Atmospheric pressure plasmas
- Plasmas in agriculture and medicine
- Corona treatments and industrial applications of plasmas

Tentative list of invited speakers (To be confirmed)

Adriana Mrquez (University of Buenos Aires) David B. Graves (University of California, Berkeley) Peter P. Sun (University if Illinois) Cristina Canal Barnils (Escola Tenica Superior de Barcelona) Dayun Yan (Geoge Washington University) Gregory Fridman (Drexel University) Sander Bekeschus (Leibniz-Institute for Plasma Science and Technology) Christopher Muratore (University of Dayton).

Symposium Organizers

Elidiane C Rangel (Laboratory of Technological Plasmas, Unesp.) Lucia vieira (Univap) R. Mohan Sankaran (Case Western Reserve University) Clodomiro Alves Jr. (UFERSA) Nilson C Cruz (Laboratory of Technological Plasmas).

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XIX Brazil MRS Meeting